

**REMARKS**

Reconsideration and allowance of the subject application in view of the foregoing amendments and the following remarks is respectfully requested.

By this Amendment, claims 6 and 9-13 are amended to at least correct minor grammatical errors. Accordingly, claims 1-13 are pending in this application of which claims 1-5 have been withdrawn.

Claims 6-8 stand rejected under 35 U.S.C 103(a) variously, as being unpatentable over Ballantine et al. (US 6,488,778), and one or more of Shao et al. (US 6,437,290), and Tsao (US 4,752,815).

In response, claim 6 is amended, and as presented below, is believed to be patentable over the applied art for the failure of the applied art to not only disclose, teach or suggest all of Applicants' recited claim features, but in addition failure to present any apparent reason to combine references or modify prior art to create the Applicants' allegedly obvious claim elements.

More specifically, claim 6 is amended to recite a method for manufacturing a semiconductor device, comprising, *inter alia*, "...depositing a metal film by said metal depositing portion by sputtering, wherein a sputter shutter prevents the metal to be deposited from being spread on sides thereof..." The above-mentioned features are believed to be supported by at least Fig. 3 and the accompanying text in paragraph [0036]. Applicants respectfully submit that this feature is not disclosed, taught or suggested by the applied references, taken alone or in combination.

Therefore, Applicants respectfully submit that claim 6 is patentable at least due to the failure of the applied references to disclose, teach or suggest all recited features of the claim. Claims 7-8 depend from independent claim 6 and are likewise patentable over the asserted combination of references for at least their dependence on an allowable base claim, as well as for the additional features they recite.

Claims 9-14 stand rejected under 35 U.S.C 103(a) as being unpatentable over Ballantine, Shao, Tsao, and further in view of one or more of Beinglass (US 5,940,733), Brabant et al. (US 2003/0036268), Chang et al. (US 5,043,299), Adetutu (US 5,958,508), Aoki (US 5,242,666), and Yamoto et al. (US 6,399,429).

Applicants amend independent claim 9 to similarly recite a sputtering operation moving the substrate in a downward direction and heating the substrate to form a silicide, after depositing the metal film. Applicants method, as recited in claim 9, is distinguished from the applied references in that Ballantine appears to only disclose wherein the heating process is carried out by moving the wafers upward into the chamber 50, (*see* Abstract, lines 22-25).

Claims 10-14 depend from independent claim 9 and are likewise patentable over the asserted combination of references for at least their dependence on an allowable base claim, as well as for the additional features they recite.

### **Conclusion**

All objections and rejections having been addressed, it is respectfully submitted that the present application should be in condition for allowance and a Notice to that effect is earnestly solicited. Early issuance of a Notice of Allowance is courteously solicited.

The Examiner is invited to telephone the undersigned, Applicants' attorney of record, to facilitate advancement of the present application.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 07-1337 and please credit any excess fees to such deposit account.

Respectfully submitted,  
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